



Iris AO, Inc.

MEMS Segmented DM Development in Support of Exoplanet Missions

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NNG07CA06C Phase II SBIR Technology Advances

Jan 2007 – May 2009

30 X Increase in DM Positioning Resolution

- Prior to SBIR: 14.8 nm *rms* on 5 μ m-stroke DM
 - Limited by electronics noise
- After SBIR: 0.5 nm *rms* (1.8 nm LSB), on 6 μ m-stroke DM
 - Limited by 14-bit drive electronics resolution and DM stroke

Electronics Development

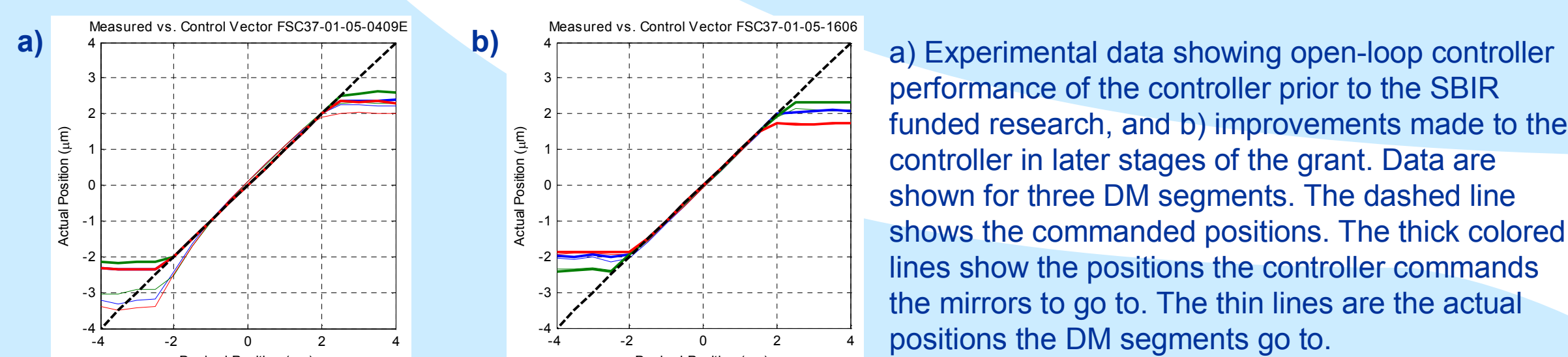
- Low noise, 14-bit drive electronics developed and commercialized
 - Units sold within 10 months of starting Phase II research
- > 10X reduction in broadband noise compared to 1st generation drive electronics
- > 30X reduction in band-limited noise (< 2kHz)
 - Noise floor below 14-bit resolution



DM Design Modified

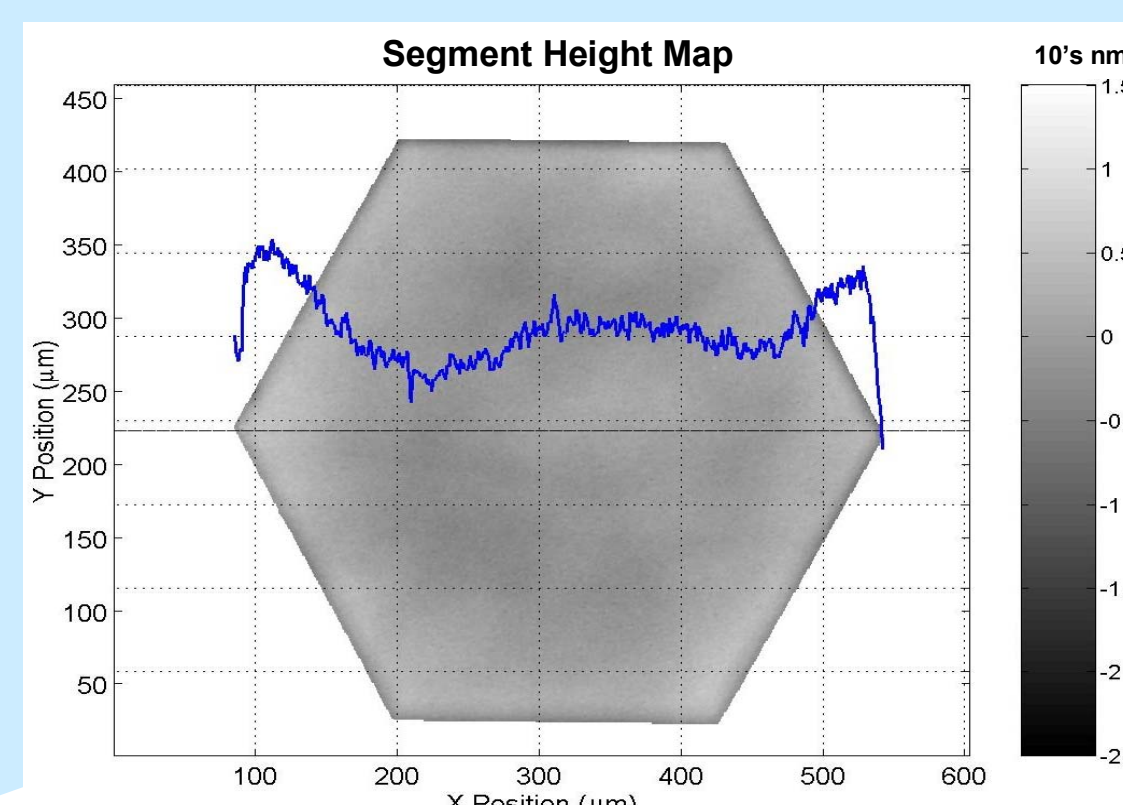
- Design modified to use more of the electronics dynamic range
- Prior to SBIR, 5 μ m stroke DMs operated with ~60V
- After SBIR, 6 μ m-stroke DMs operate with 120V

Improved Open-Loop Control



Improved DM Flatness

- Prior to SBIR: Segment flatness varies 6-20 nm *rms* across DM and from DM to DM
 - Segments w/ ~2nm *rms* have been demonstrated
- After SBIR: Goal of 1-3 nm *rms* across DM and from DM to DM
 - Tests will be complete May 2009

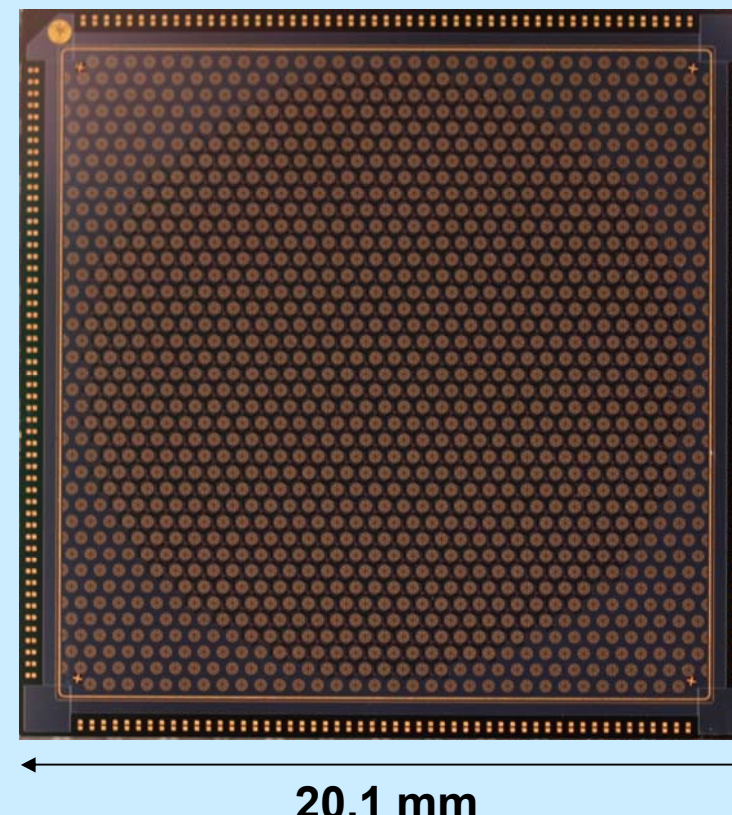


Segment Flatness – 2.13 nm *rms*

DM Scaling

- Prior to SBIR
 - 37 segment DM
 - 128-channel drive electronics
- After SBIR:
 - 2 process runs of 925-segment demonstration actuator array w/ ganged electrodes
 - 128 & 512-channel drive electronics
 - USB interfaced electronics can be daisy chained to run >10k channels

925-Segment Actuator Array



20.1 mm

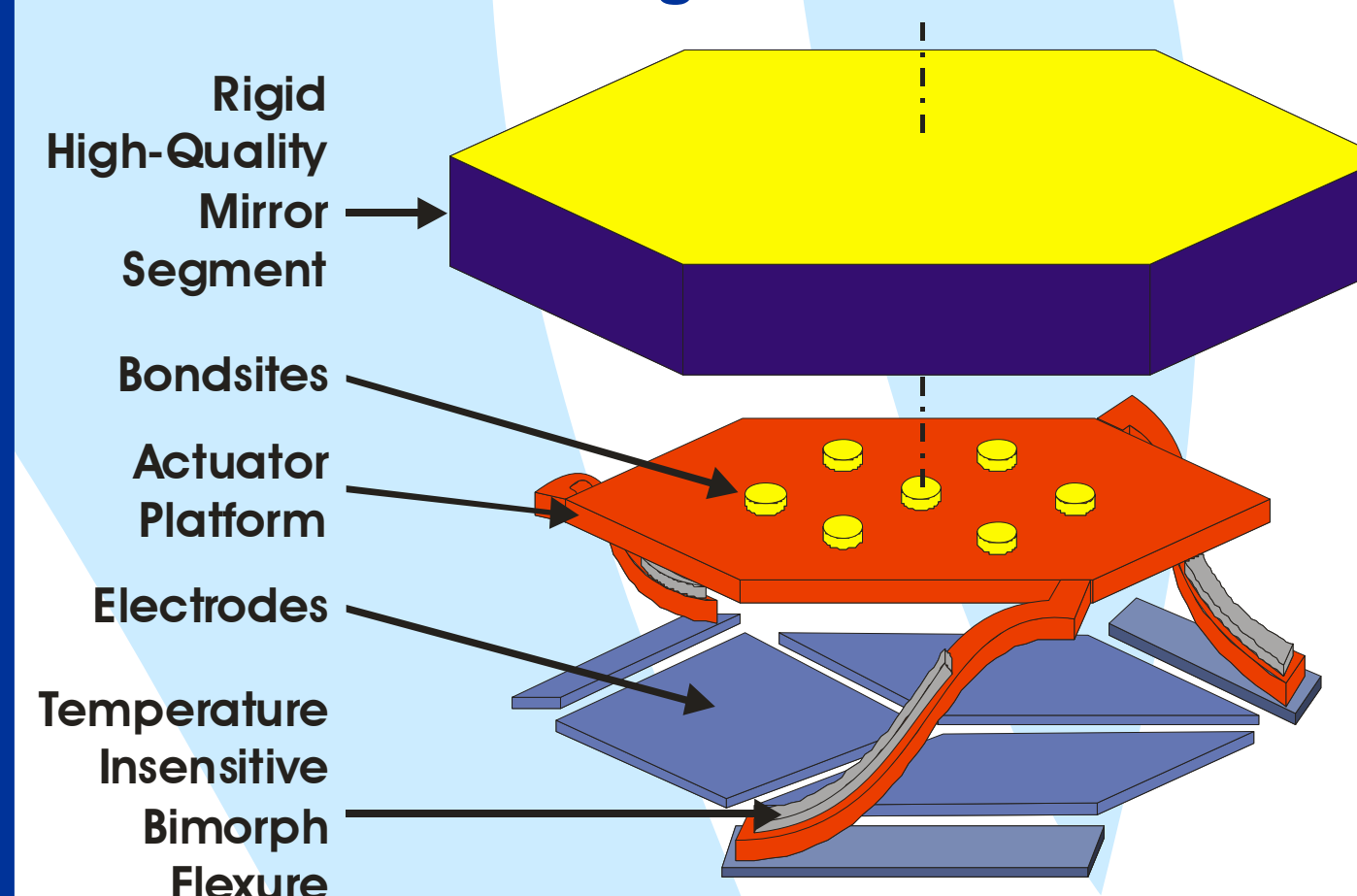


Iris AO Product Line

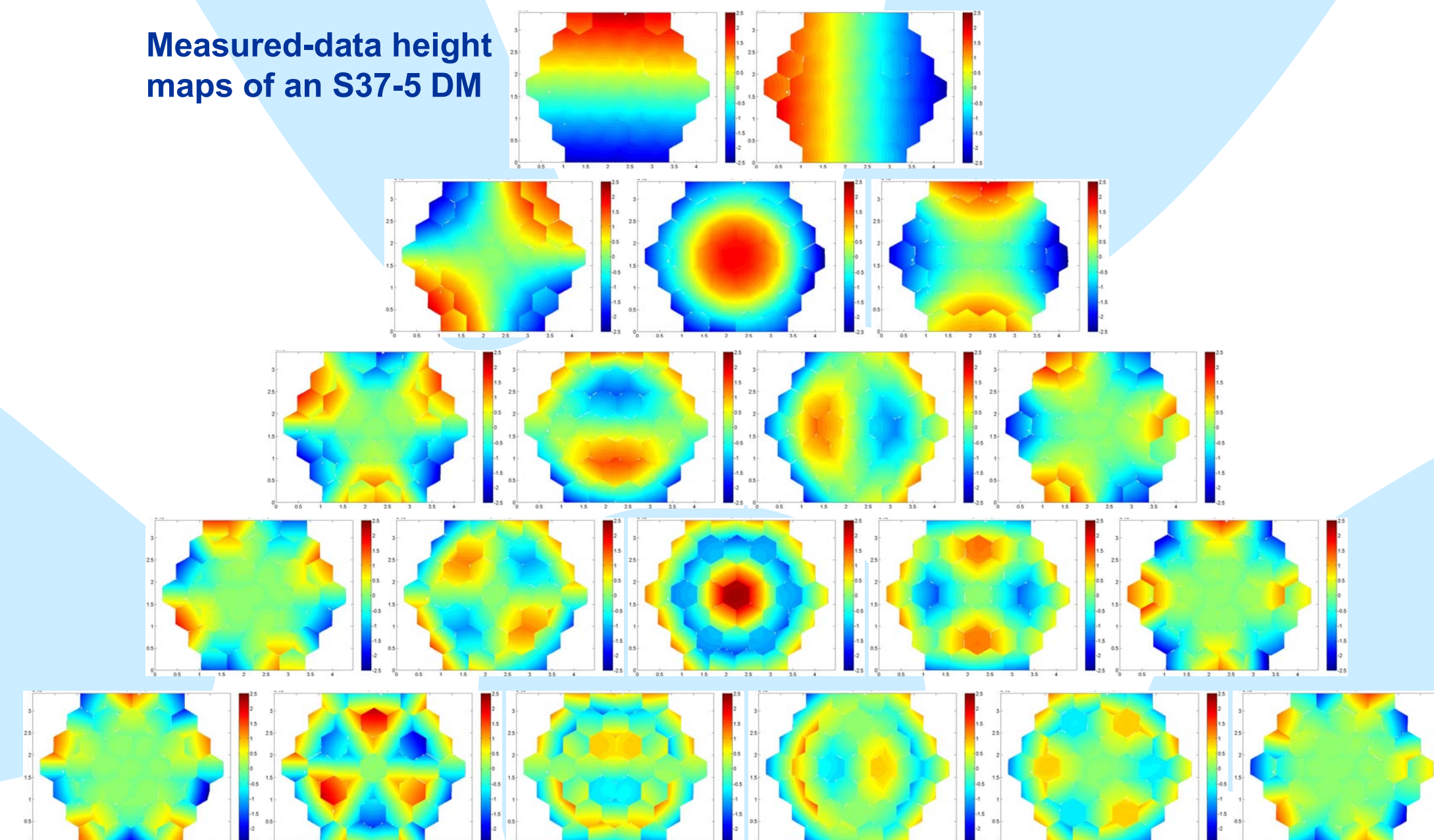
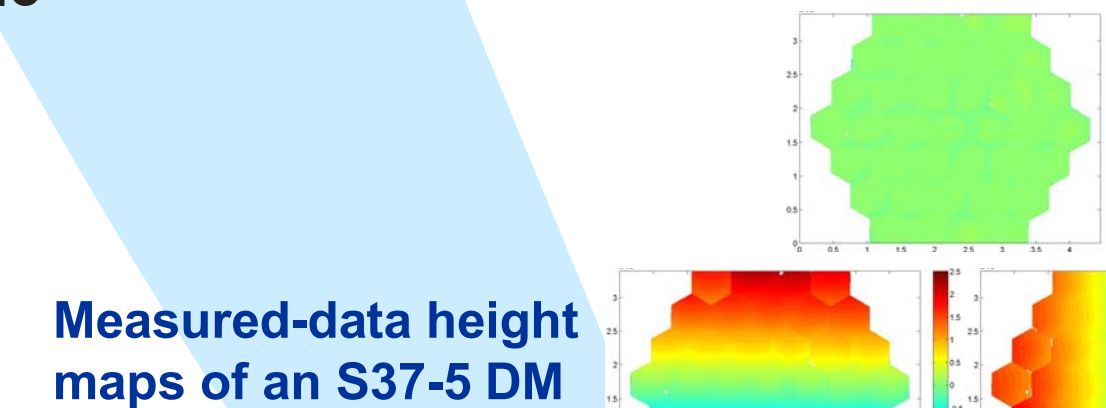
S37-X: Easiest to Use DM on the Market

- Intuitive interface: User specifies mirror position instead of voltages
 - Positions specified as segment PTT values or Zernike coefficients for entire DM
- Factory calibrated piston/tip/tilt controller enables excellent open loop positioning
 - Mirror position is linear and accurate
- No coupling between segments and excellent open loop control simplify closed-loop control and improve closed-loop performance
 - No wasted control-loop samples to iterate to best correction means higher correction bandwidth
- Unique hybrid design enables use of thick, high optical quality segments

Iris AO DM Segment Schematic

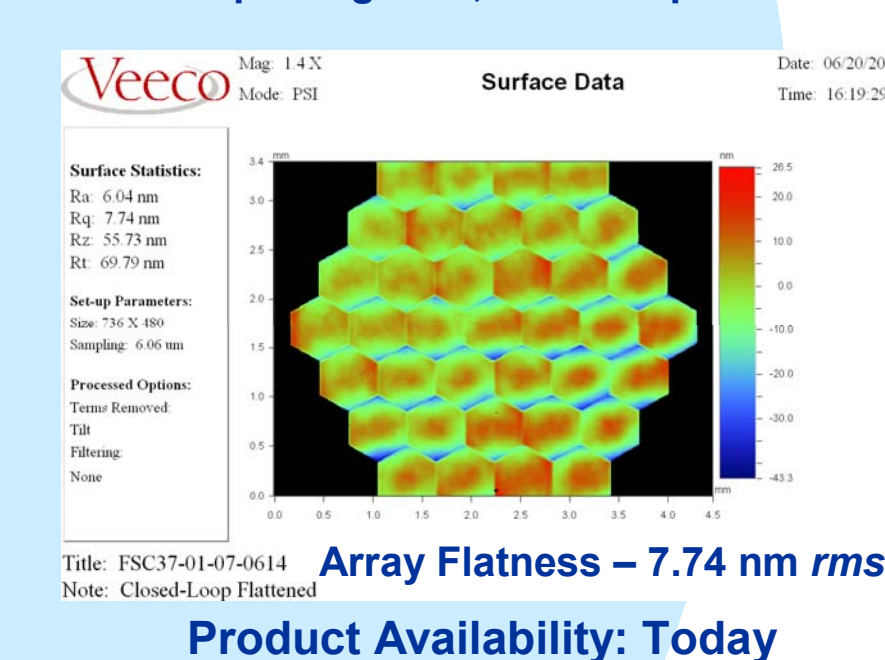


S37-X DM Die Photo



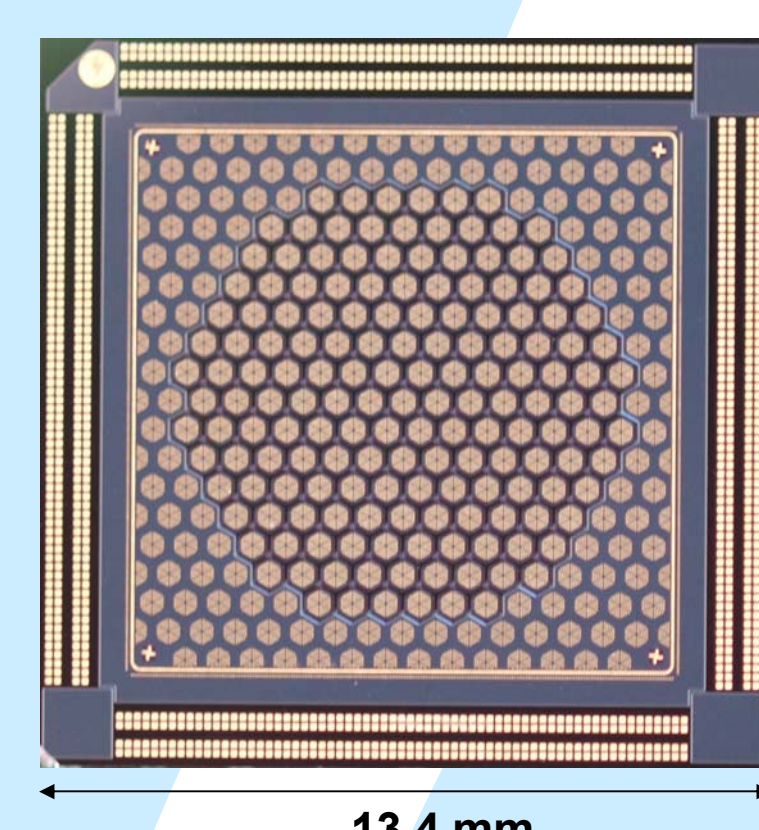
DM Roadmap

S37-X, 111 actuator, 37 segment DM
700 μ m segment, 3.5 mm aperture



Array Flatness – 7.74 nm *rms*
Product Availability: Today

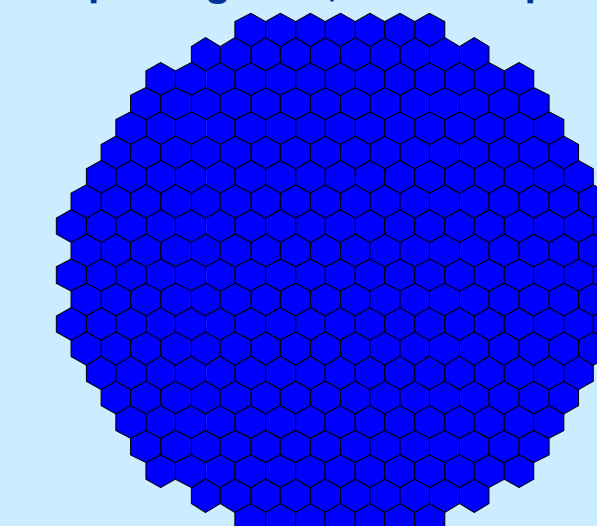
S163-X, 489 actuator, 163 segment DM
700 μ m segment, 7.7 mm aperture



13.4 mm

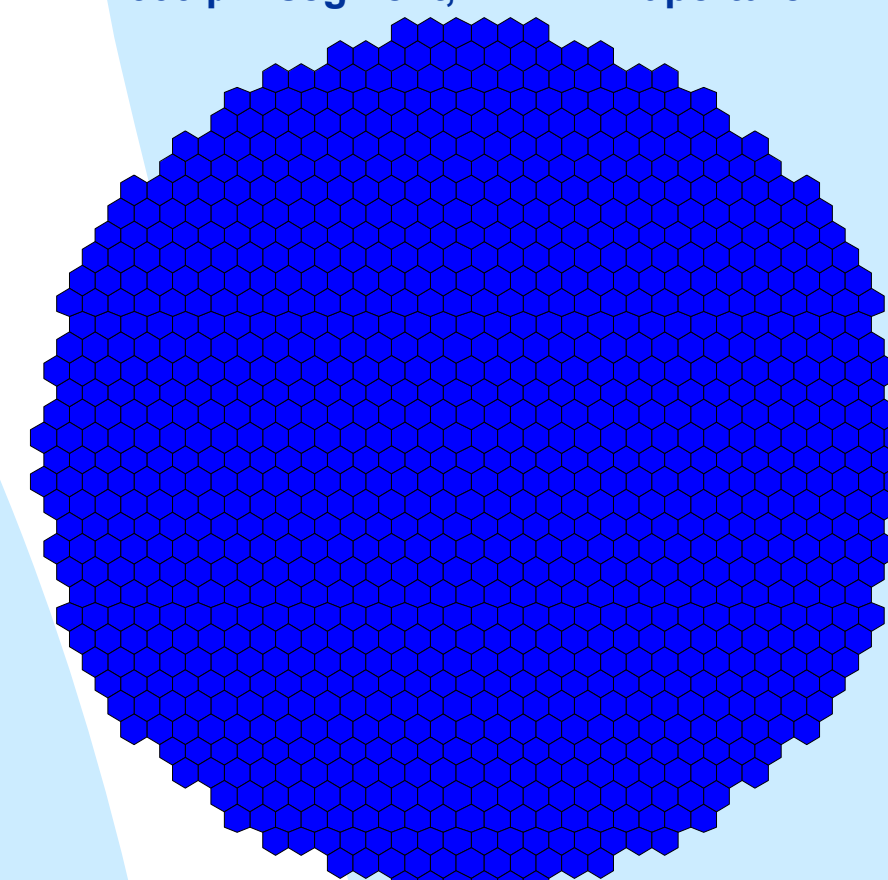
Availability: Sept 2009 (Beta) , Sept 2010 (Product)

S313-X, 939 actuator, 313 segment DM
600 μ m segment, 9.9 mm aperture



Availability: Jan 2012 (Beta) , Jan 2013 (Product)
Pending Funding

S1015-X, 3045 actuator, 1015 segment DM
600 μ m segment, 17.1 mm aperture



Availability: Jan 2013 (Beta) , Jan 2014 (Product)
Pending Funding

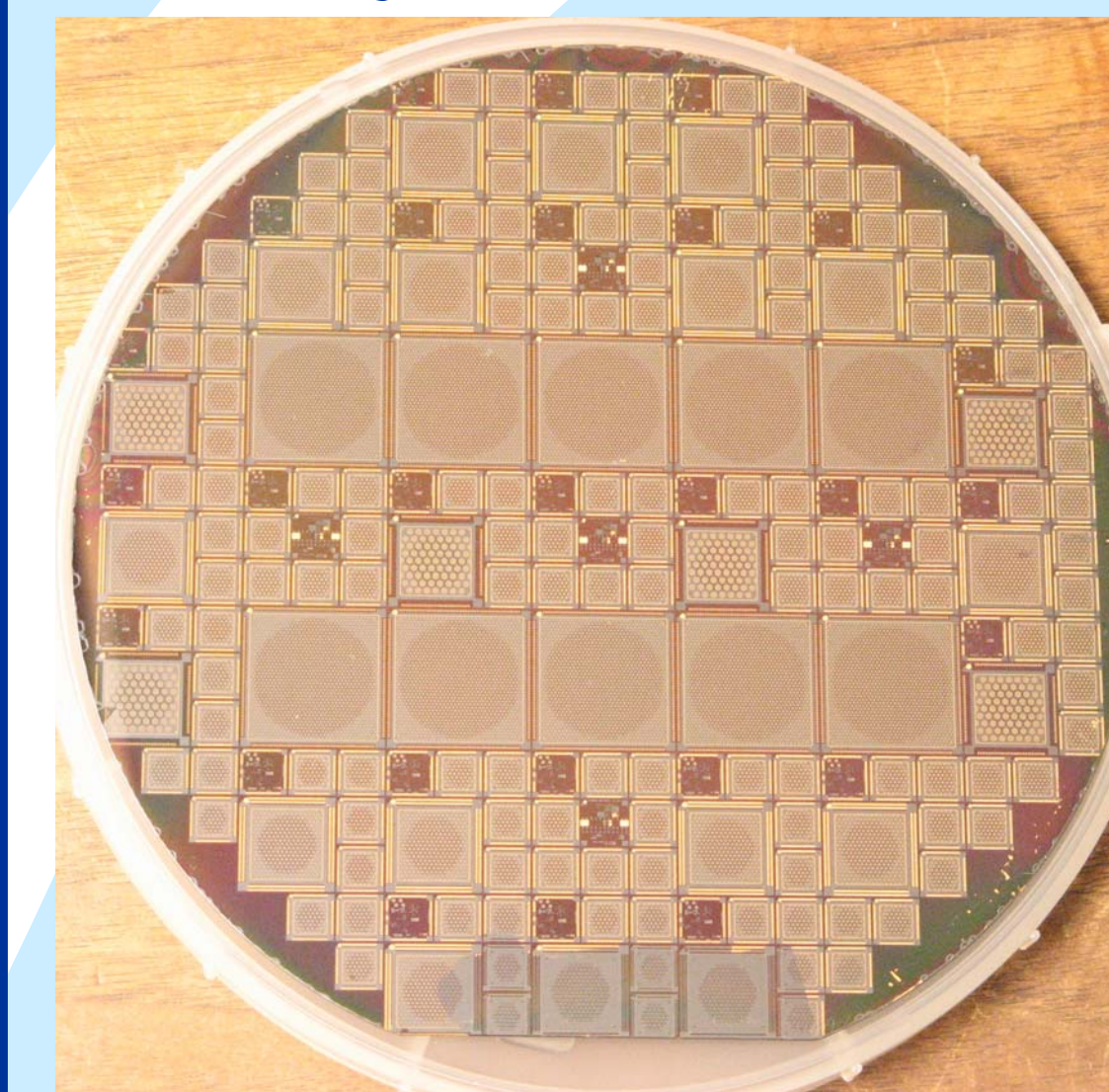
NNX09CE01P Phase I SBIR and Proposed Phase II SBIR Technology Objectives

Jan-July 2009

Phase I Objectives

- Further develop MEMS fabrication processes for large DM arrays
- Demonstrate ability to wire to 3000+ actuators on MEMS chip
- Quantify yield reducers
- Propose process improvements
- Demonstrate assembly and operation of 925-segment array
 - Array has ganged electrodes

Multi-Project Actuator Wafer Partially Funded by Phase I Research



- 37, 163, and 925 segment actuator arrays built on same wafer
- 37 and 163 segment designs are complete
- 925-segment demonstration design with ganged electrodes
- Costs spread across multiple projects for early development
- Wafer shown has mechanical layers only
- Wafer with electrodes and wiring currently being fabricated

Proposed Phase II Objectives (proposal to be submitted July 2009)

- **Hardware Deliverable:** Fully wired S331-X DM
 - Lower stroke to increase resolution
 - Reduced electrode sizing to use full dynamic range of electronics and increase resolution
- Improve fabrication process to increase segment yield
- Design and fabricate fully wired S1013-X DM
 - Packaging beyond the scope of a single Phase II SBIR
 - Funding source TBD

Additional Development at Iris AO

- High-speed (5 kHz) electronics interface
- Protected-silver coatings
- Dielectric coatings
 - Mirror segments fabricated with stress compensation layer to counteract stresses from thick (1-3 μ m) dielectric coatings
- Environmental testing

SBIR Commercialization Path

Most of the DM and electronics technologies developed under NASA SBIR NNG07CA06C have been instrumental in developing the S37-X DM. The Phase I research currently underway (NNX09CE01P) and the Phase II research to be proposed will expand the Iris AO product line by supporting process development critical to the S163-X and by developing the S331-X DM. Revenues from these products will be reinvested into IR&D to continue the development of high-performance DMs.

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